

16. (New) A substrate preparing device according to claim 15, further comprising:
a gas ionizer constructed and arranged to ionize said gas bearing.
17. (New) A substrate preparing device according to claim 15, further comprising:
a position detector constructed and arranged to detect a first position of said substrate on said intermediate table;
a displacement calculator constructed and arranged to calculate a required displacement between said first position and a desired position of the substrate on the intermediate table; and
an actuator constructed and arranged to move said substrate from said first position to said desired position.
18. (New) A substrate preparing device according to claim 15, wherein said gas bearing generator comprises:
a gas source arranged to deliver gas through said plurality of apertures to generate the gas bearing; and
an evacuation pump arranged to evacuate the gas from the gas bearing.
19. (New) A substrate preparing device according to claim 15, wherein said substrate preparing device is a part of a resist processing apparatus.
20. (New) A substrate preparing device according to claim 12,
wherein said intermediate table further comprises a first temperature controller constructed and arranged to regulate a temperature of the intermediate table.
21. (New) A substrate preparing device according to claim 20,
wherein said first temperature controller maintains the intermediate table and the gas bearing at a temperature substantially equal to a temperature of the substrate table.
22. (New) A substrate preparing device according to claim 12,
wherein said intermediate table further comprises a second temperature controller constructed and arranged to regulate a temperature of said gas bearing.

23. (New) A substrate preparing device according to claim 12, further comprising:
a position detector constructed and arranged to detect a first position of said substrate on said intermediate table;
a displacement calculator constructed and arranged to calculate a required displacement between said first position and a desired position of the substrate on the intermediate table; and
an actuator constructed and arranged to move said substrate from said first position to said desired position.
24. (New) A substrate preparing device according to claim 12, wherein said substrate preparing device is a part of a resist processing apparatus.
25. (New) A device manufacturing method according to claim 10, further comprising:
ionizing said gas bearing with a gas ionizer.
26. (New) A device manufacturing method according to claim 10, further comprising:
regulating a temperature of said intermediate table with a first temperature controller.
27. (New) A device manufacturing method according to claim 10, further comprising:
regulating a temperature of said gas bearing with a second temperature controller.
28. (New) A device manufacturing method according to claim 10, further comprising:
maintaining said intermediate table and the gas bearing at a temperature substantially equal to a temperature of the substrate table.
29. (New) A device manufacturing method according to claim 10, further comprising:
detecting a first position of said substrate on said intermediate table;
calculating a required displacement between said first position and a desired position of the substrate on the intermediate table; and
moving said substrate from said first position to said desired position.